

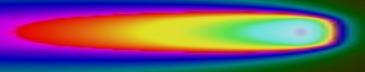
# Investigating a Few Remaining Unknowns of Reactive Multilayers affecting Ignition and Self-Propagating Reactions

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Sandia National Laboratories

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MRS (Boston)  
November, 2017



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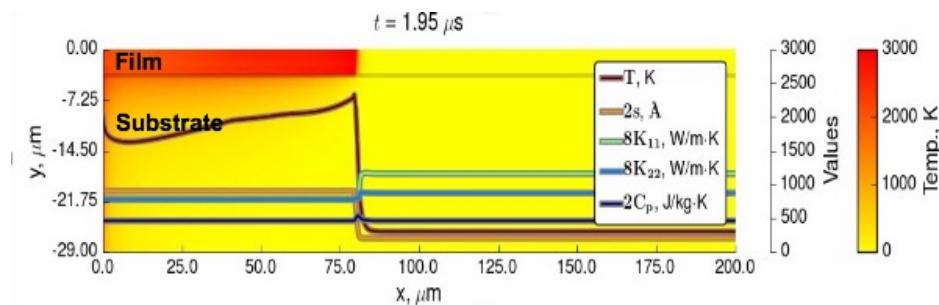
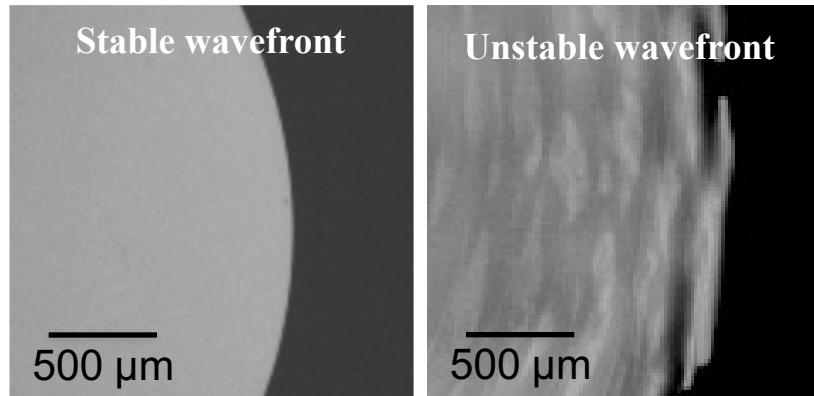
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# Reactive films and blanket coatings are of interest for several applications.

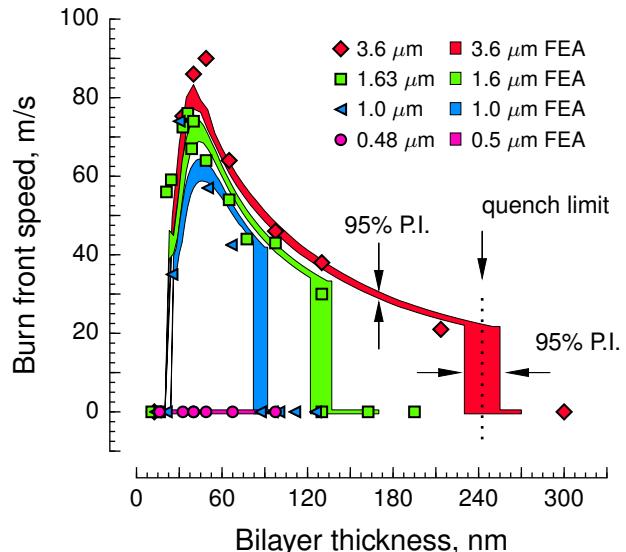
Joining by soldering (~10s of  $\mu\text{m}$ )

Heat sources for energy (~10s  $\mu\text{m}$ )

*Wavefront stability is important to reliable use*



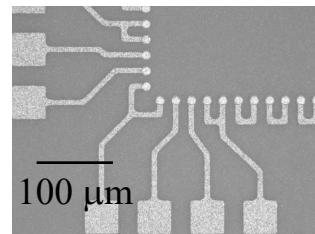
Finite Element Simulations of Al/Pt reacting on substrate: David Kittell (Sandia)



# Processing presents numerous alternatives for design but with associated challenges.

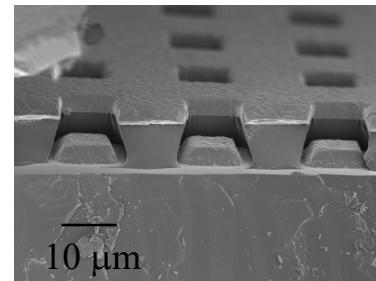
## Physical vapor deposition

$10^{-9}$  -  $10^{-7}$  Torr base pressure  
> 99 % uniformity across 6" dia.  
Maintain low temperature  
Precision: ~1 nm  
Various materials

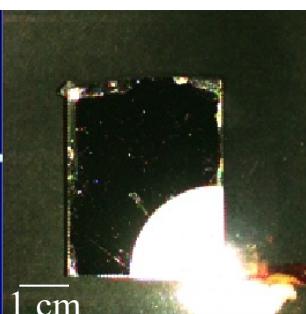
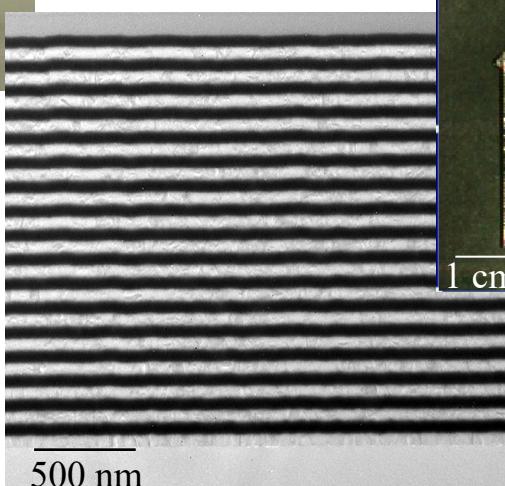


## Photolithography

Feature definition by liftoff

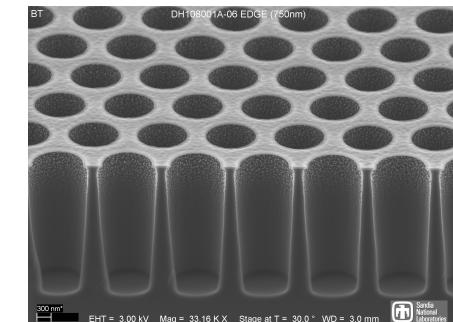


*Reactive multilayer shown by TEM in cross section*



## Bosch etching

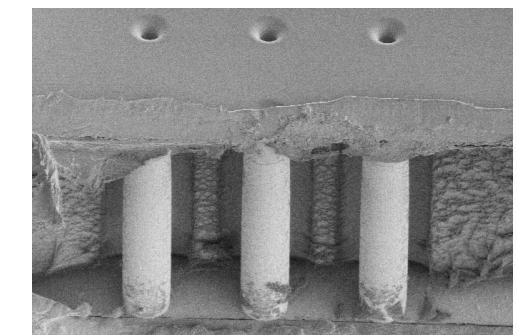
Etching submicron features in Si  
High aspect ratios



Cross Section showing partially etched holes,  $\varnothing$  = 1 micron

## Atomic layer deposition

Infiltration (few materials)  
Conformal coatings  
Angstrom level precision



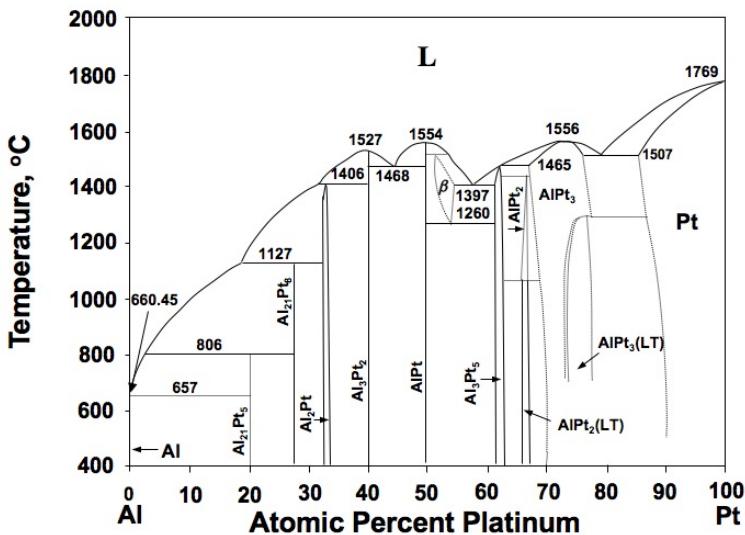
# Outline

i) A look at reactive properties across the full range of stoichiometry for the Al/Pt system

- Heats ( $\Delta H_{rxn}$ ,  $\Delta H_{Al_xPt_y}$ )
- Ignition (experiments, analytical model)
- Wave speeds (experiments, analytical model)

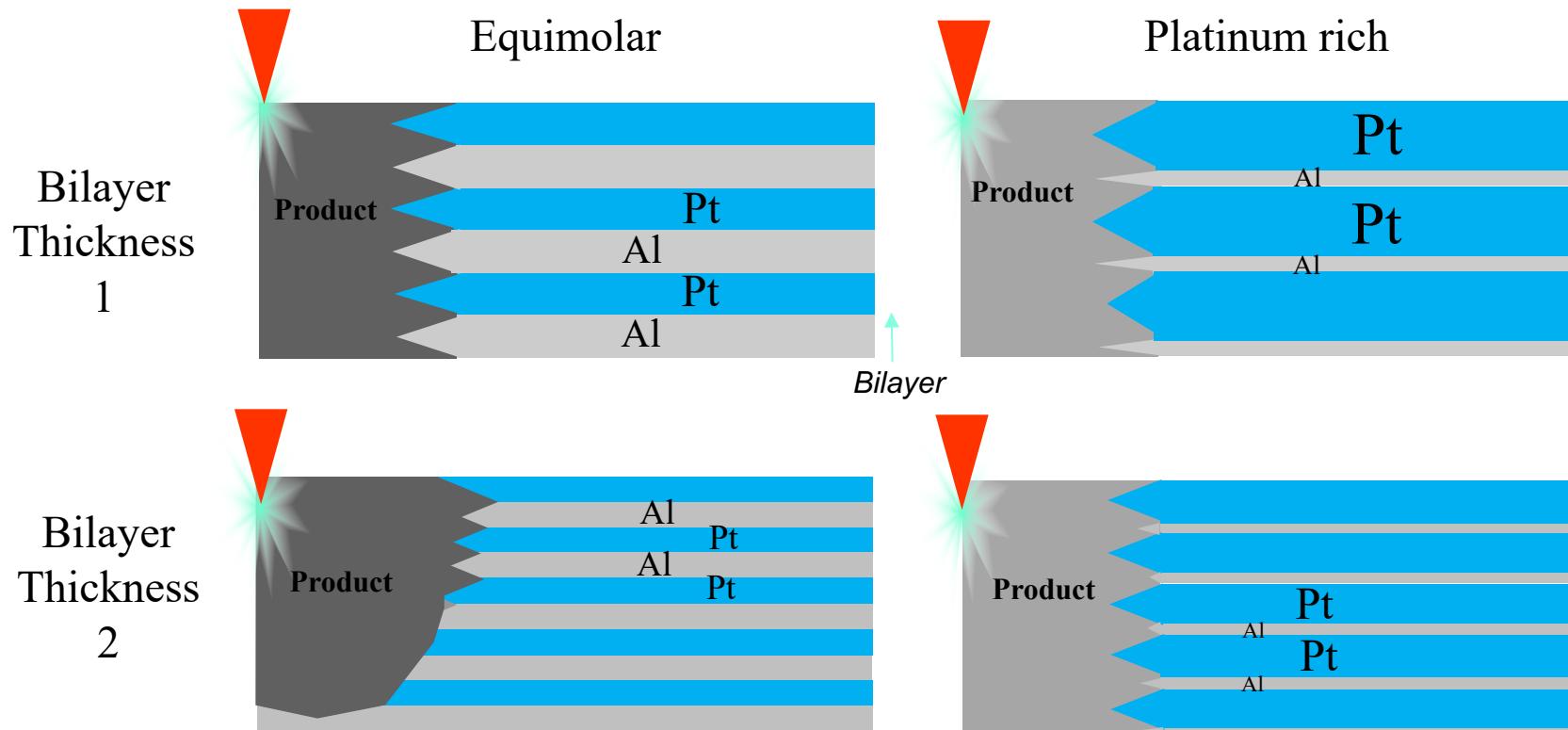
ii) Investigations of thermal conductivity by Time Domain Thermoreflectance (TDTR)

- Variation with bilayer thickness
- Changes with chemistry (Al/Pt, Co/Al, NiV/Al)



Phase Diagram redrawn from  
McAlister and Kahan, ASM 1986

Multilayers have been made with different overall stoichiometry and periodicity.

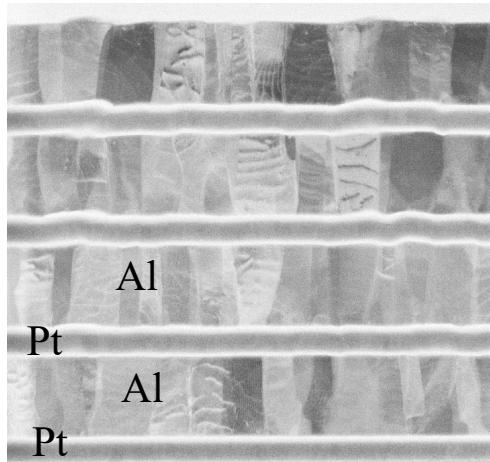


Stoichiometry varied from 9Al:1Pt to 1Al:9Pt.  
Bilayer thickness varied from 10 nm to 1600 nm.  
Total multilayer thickness fixed at 1.6  $\mu\text{m}$ .

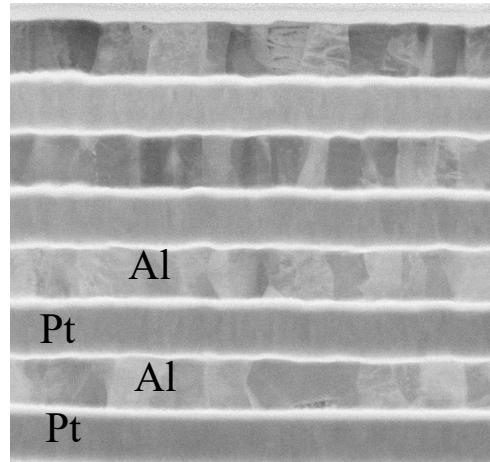
# Example multilayers are shown by SEM.

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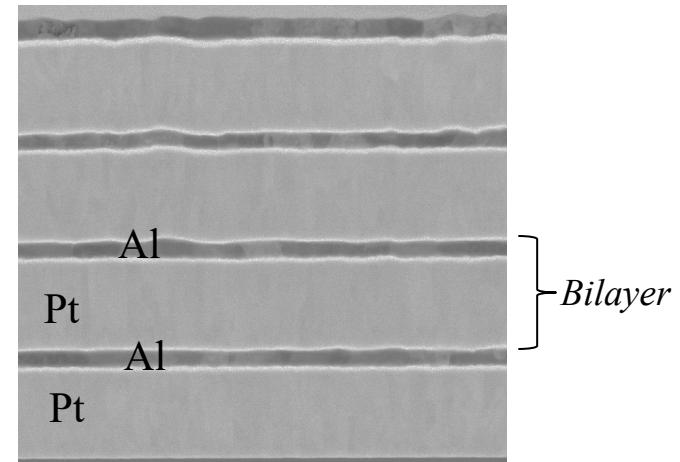
4Al:1Pt



1Al:1Pt



1Al:4Pt

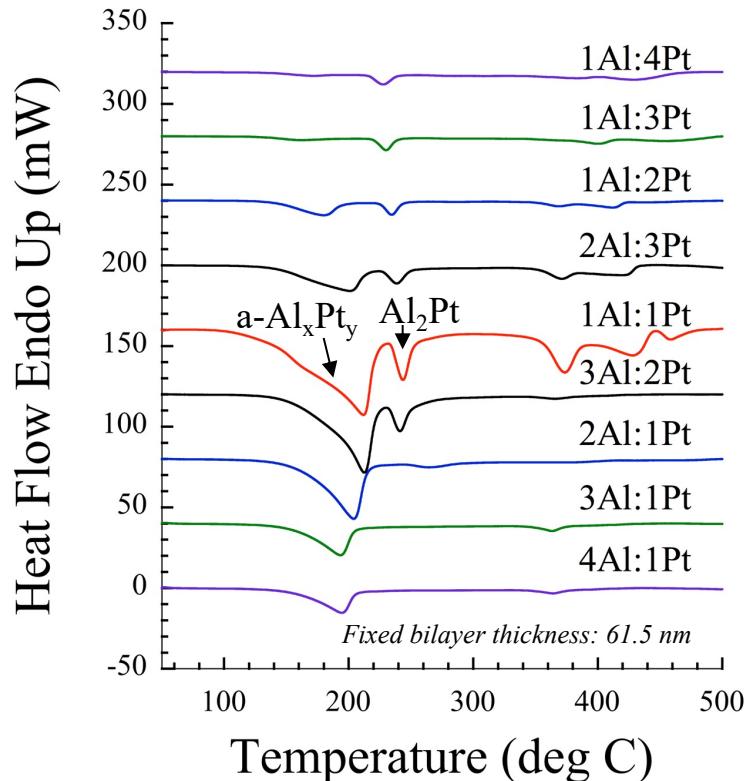


1.0  $\mu$ m

*Each has a bilayer thickness of  $\sim 400$  nm.*

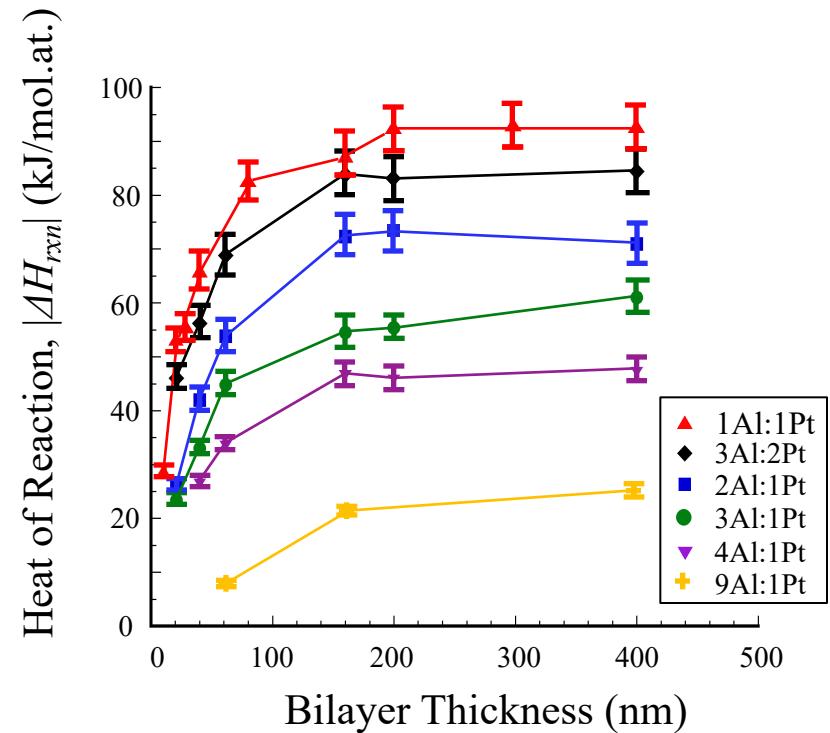
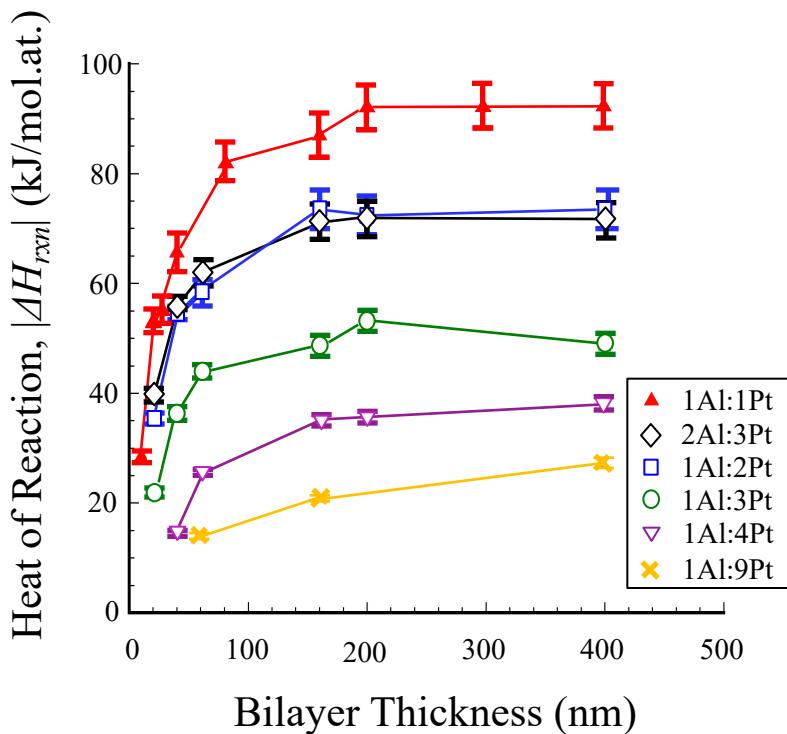
# Differential Scanning Calorimetry is used to obtain thermograms from Al/Pt.

- All  $\text{Al}_x\text{Pt}_y$  stoichiometries studied here are characterized by exothermic reactions.
- First exotherms starts at  $\sim 100^\circ\text{C}$ .
  - Separate XRD confirms growth of amorphous interlayer ( $\text{a-Al}_x\text{Pt}_y$ ) is associated with first, broad exotherm.
- Additional exotherms
  - associated with formation of different crystalline intermetallic phases (many cases starts with  $\text{Al}_2\text{Pt}$ )



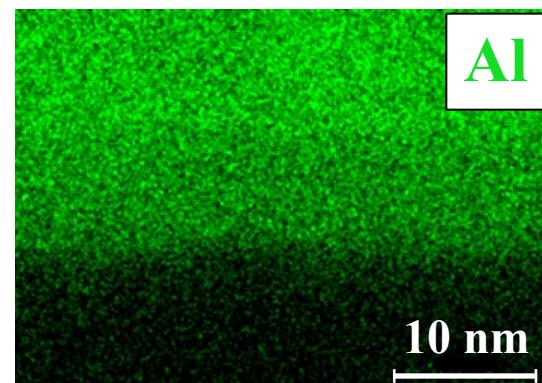
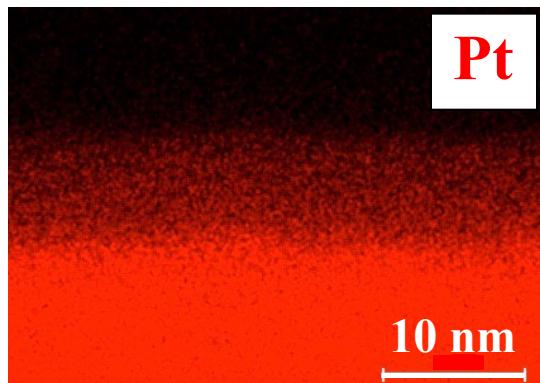
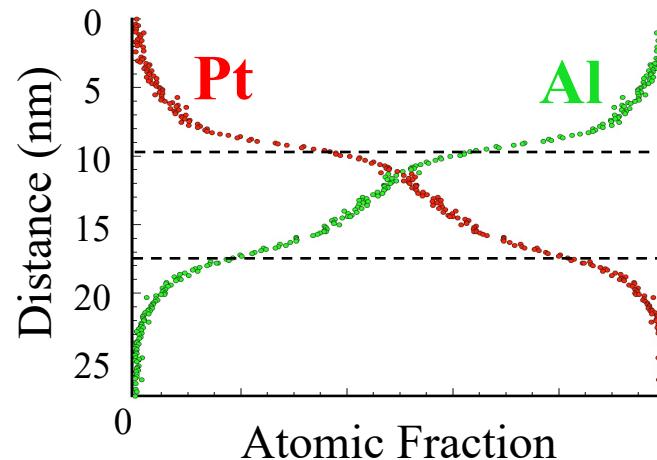
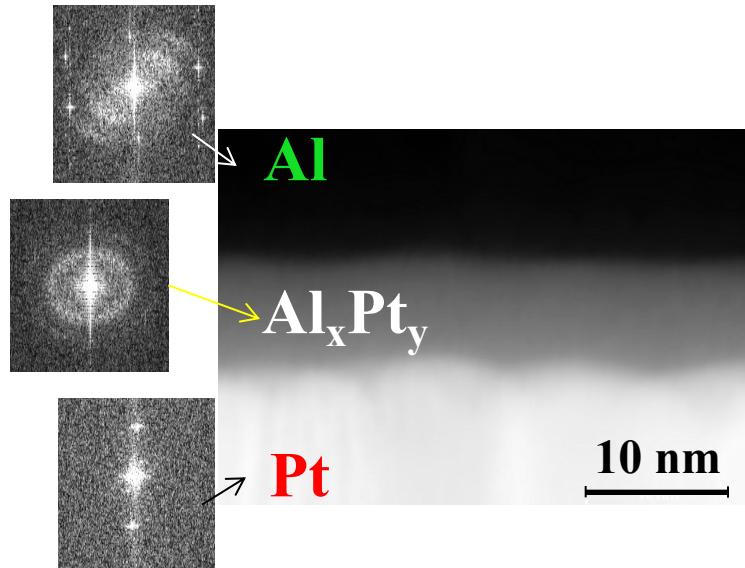
Heating rate: 40 degrees / minute  
Gaseous environment: N<sub>2</sub>  
Perkin Elmer DSC system

# Measured heats of reaction vary with bilayer thickness and stoichiometry.

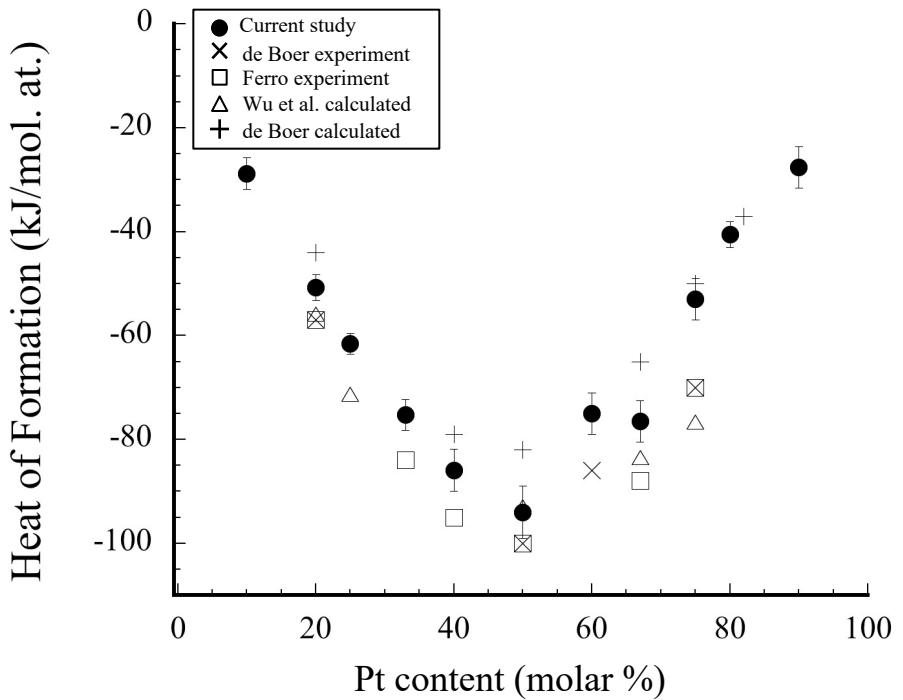
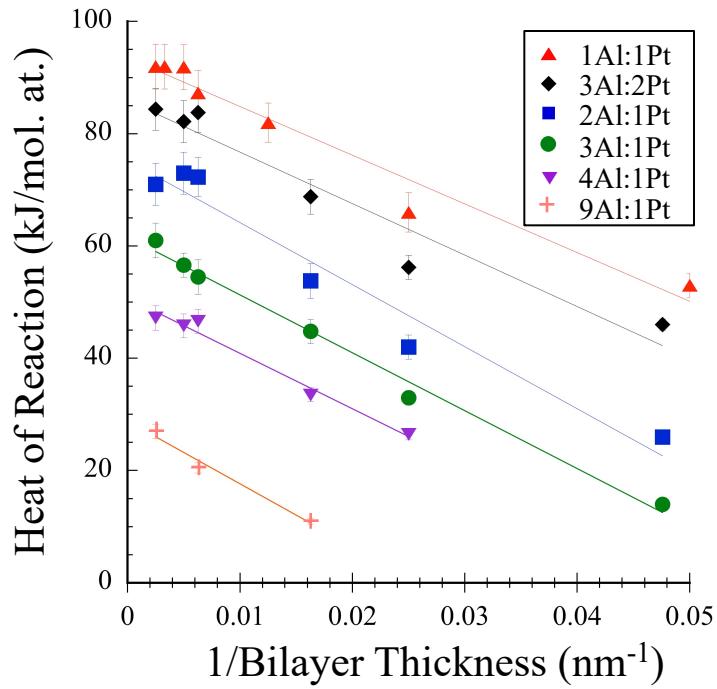


- Equimolar multilayers exhibit greatest  $|\Delta H_{rxn}|$ , when comparing multilayer of identical bilayer thickness.

# Interface structure and composition within an Al/Pt multilayer is revealed by TEM/EDS.



# Heats of formation are determined from measured heats of reaction.



$$\Delta H_{rxn} = \Delta H_{Al_xPt_y} - \Delta H_{premix} \left[ \frac{2 w V_{Al_xPt_y}}{t_B V_{premix}} \right]$$

Measured Heat of Reaction

Heat of Formation

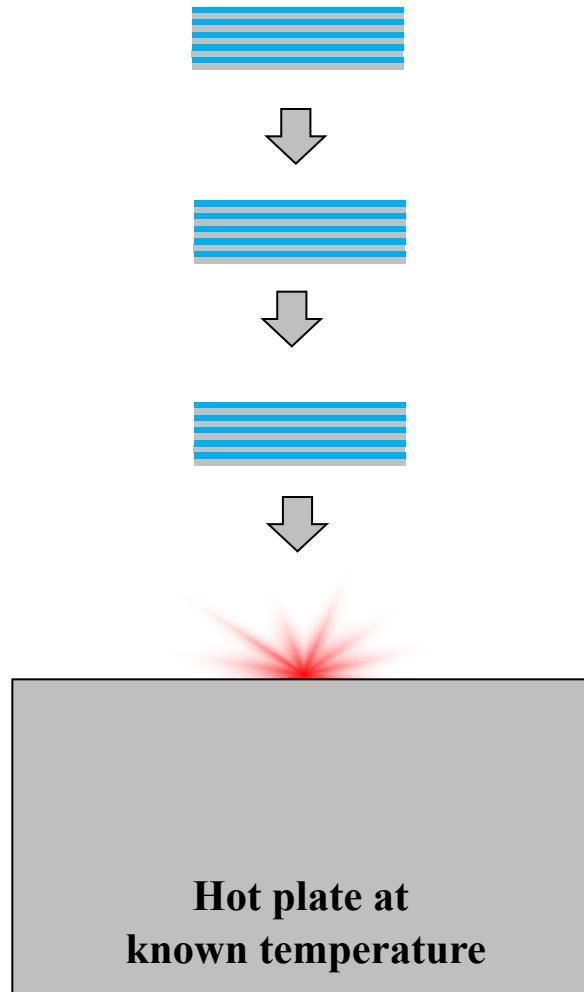
Amount lost via premixing

w = premix thickness  
 t<sub>B</sub> = bilayer thickness  
 V = molar atomic volume

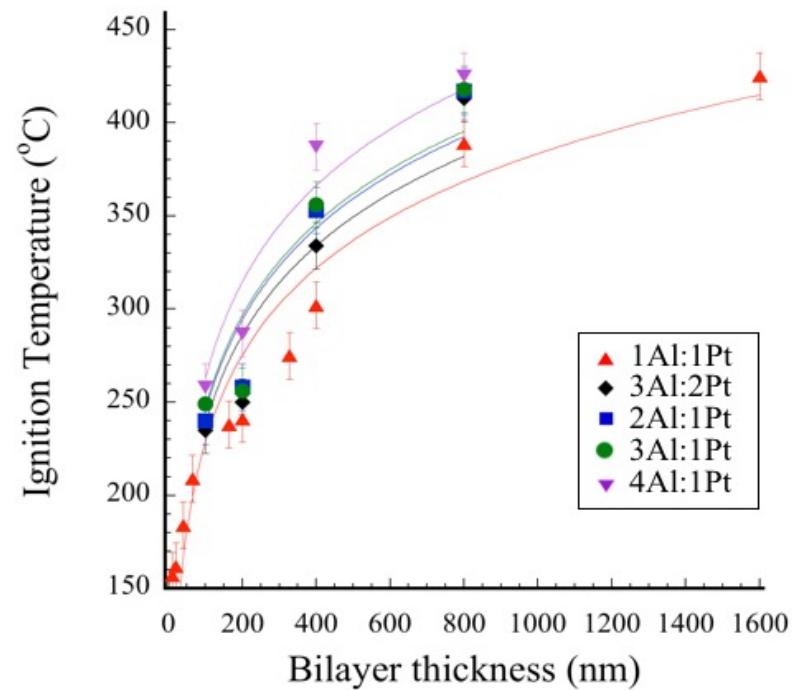
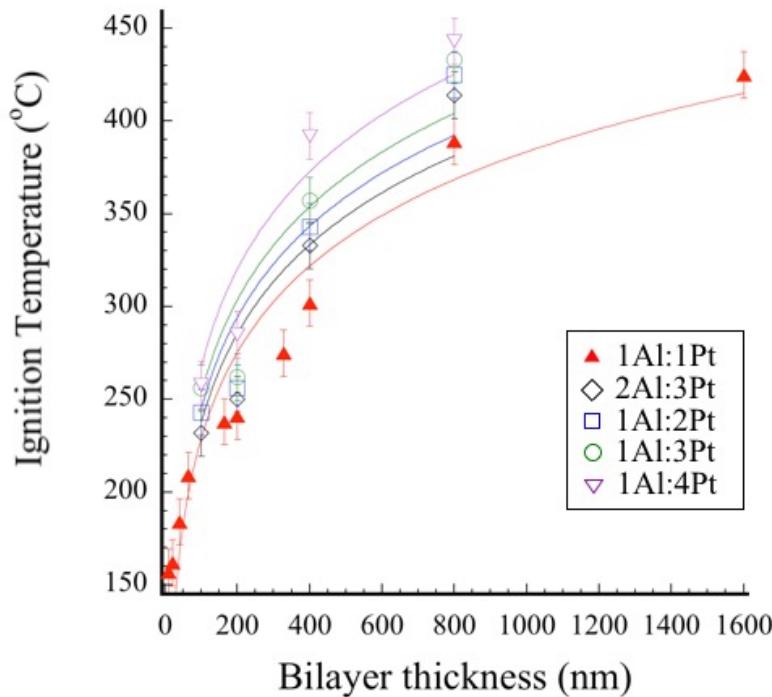
# Thermal ignition experiments

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- Equilibrate hotplate at known temperature (in air)
- 1 mm<sup>2</sup> sample is tossed onto hotplate to contact on planar face
- Observed during contact to view one of two behaviors:
  - Ignition (evidenced by bright flash and burst into microscopic debris).
  - No ignition (subtle changes in shape, slight discoloration due to oxidation)



# Ignition temperature ( $T_{ig}$ ) varies with bilayer thickness and stoichiometry.

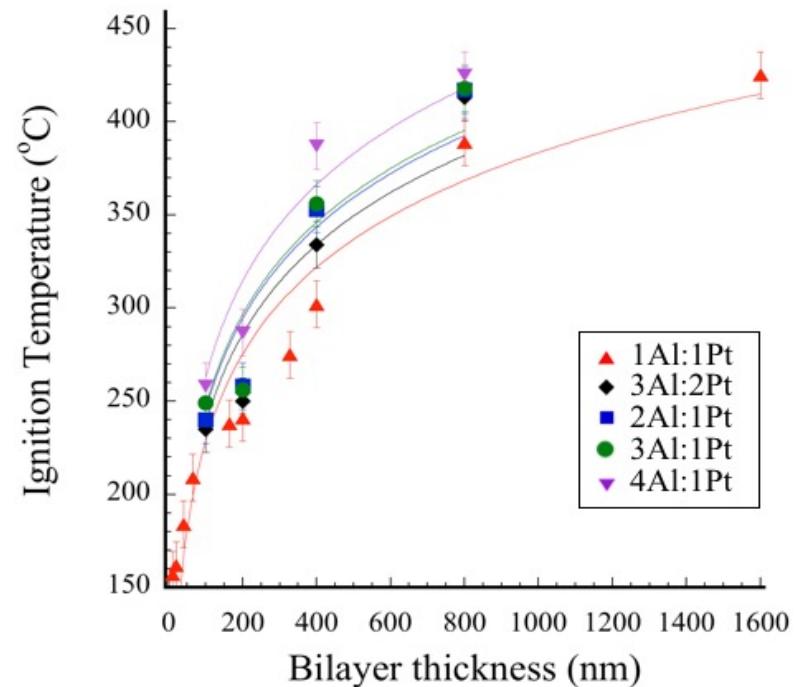


- Ignition temperature increases with bilayer thickness for each molar ratio.
- Equimolar multilayers exhibit lowest ignition temperatures.

# Logarithmic dependence of $T_{ig}$ with bilayer thickness for each stoichiometry.

Analytical expression\* for ignition temperature:

$$T_{ig} = \frac{E_a / R}{\ln \left[ \left[ \frac{2 \tau \Delta H_{rxn} D_o R_T}{t_B w} \right] \frac{f}{n(1-n)} \right]}$$



$w$  = premix thickness

$t_B$  = bilayer thickness

$\Delta H_{rxn}$  = heat of reaction

$R_T$  = thermal resistivity

$\tau$  = thickness of multilayer

$E_a$  = activation energy

$n$  = molar fraction

\*G.M. Fritz, S.J. Spey, Jr. M.D. Grapes, T.P. Weihs, J. Appl. Phys. 2013

# Activation energies associated with reactant mixing are estimated.

Analytical expression\* for ignition temperature:

$$T_{ig} = \frac{E_a / R}{\ln \left[ \left[ \frac{2 \tau \Delta H_{rxn} D_o R_T}{t_B w} \right] \frac{f}{n(1-n)} \right]}$$

$w$  = premix thickness

$t_B$  = bilayer thickness

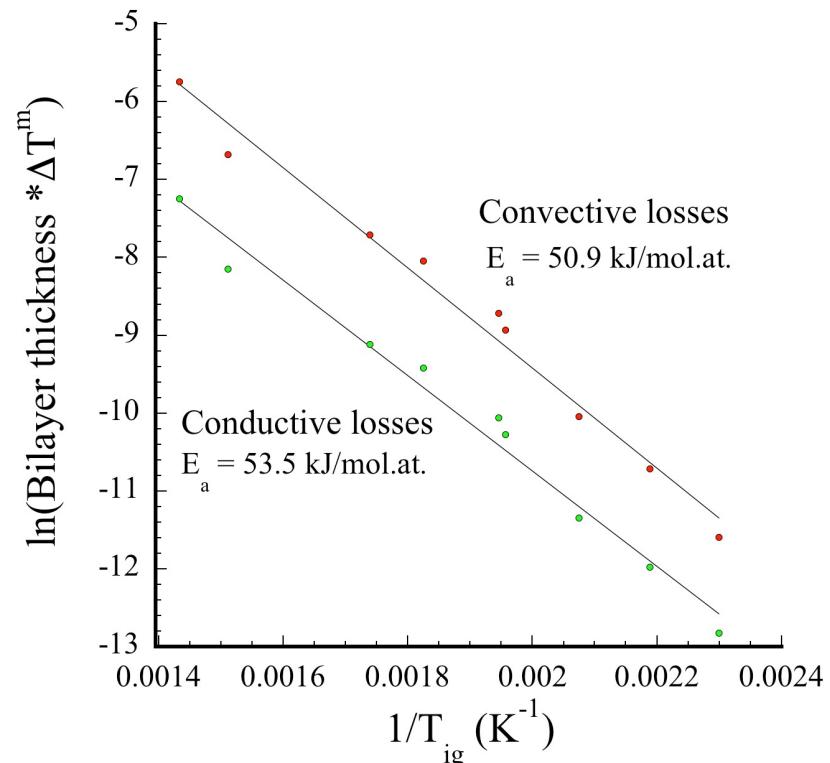
$\Delta H_{rxn}$  = heat of reaction

$R_T$  = thermal resistivity

$\tau$  = thickness of multilayer

$E_a$  = activation energy

$n$  = molar fraction



Activation energies attributed to the solid state diffusion of reactants.

\*G.M. Fritz, S.J. Spey, Jr. M.D. Grapes, T.P. Weihs, J. Appl. Phys. 2013

# High speed videography of propagating waves is used to evaluate front morphology and speed.

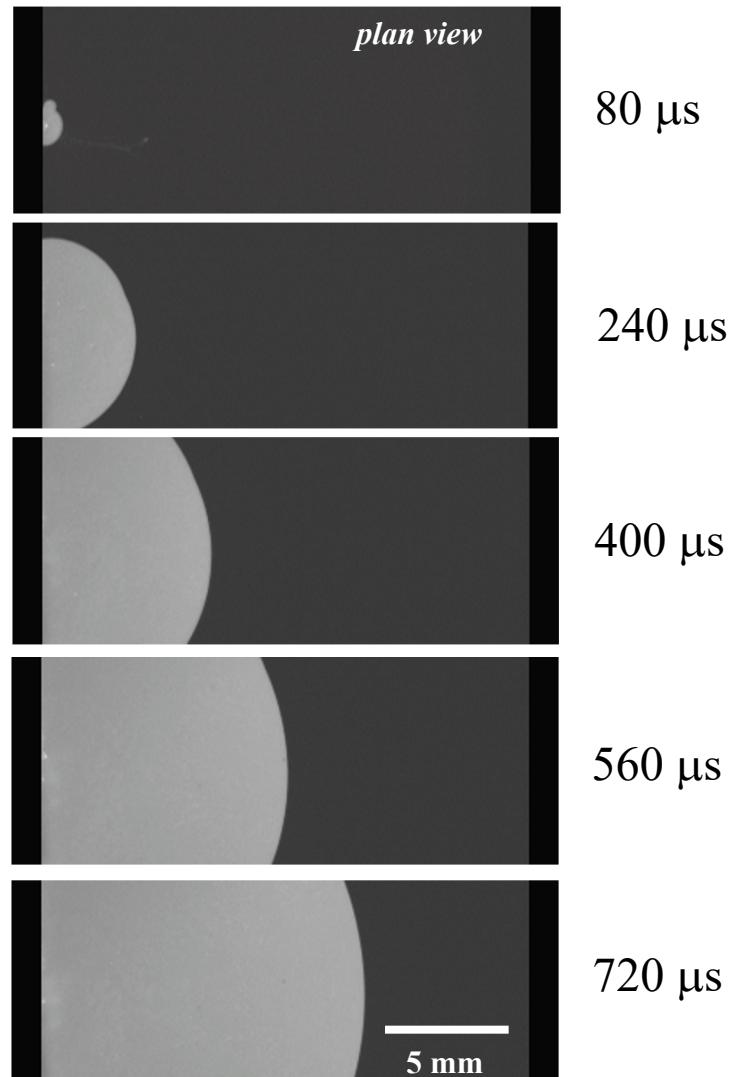
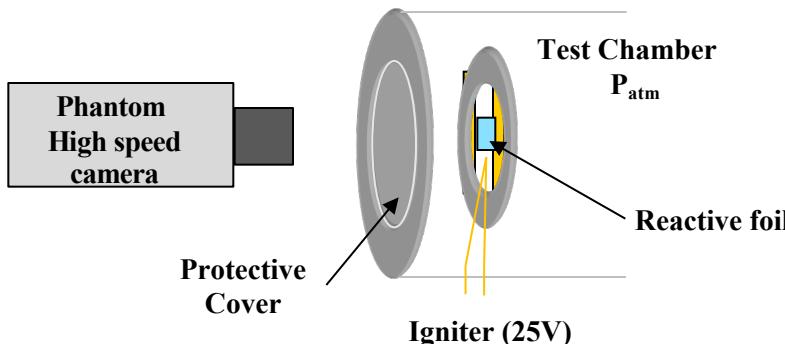
Tested as freestanding foils

Point ignition in air

No preheat above room temperature

Evaluate front position: outside ignition zone

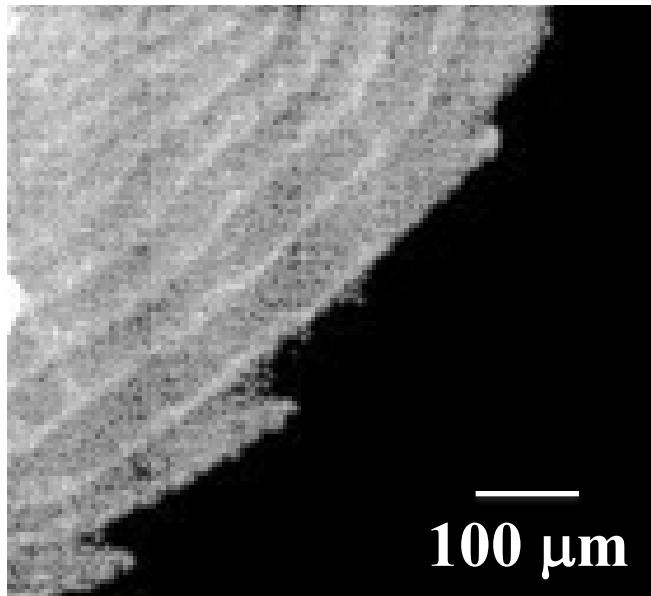
Position is plotted versus time to determine speed



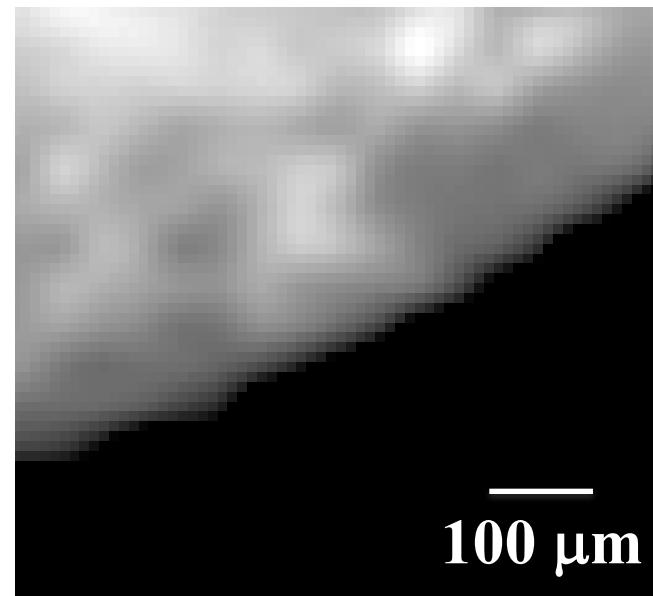
Equiatomic Al/Pt, bilayer thickness: 50 nm

Most multilayers undergo stable propagation.  
Only one design, near a limit of stoichiometry,  
exhibited an instability.

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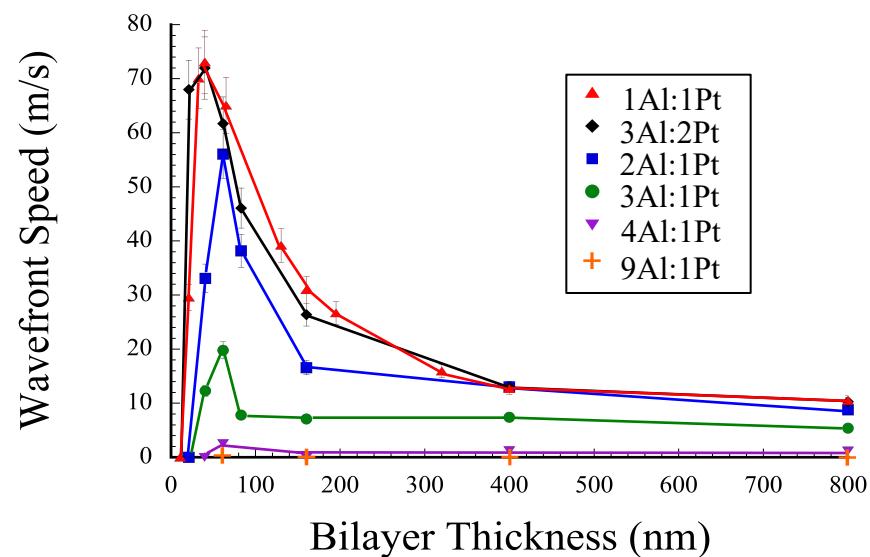
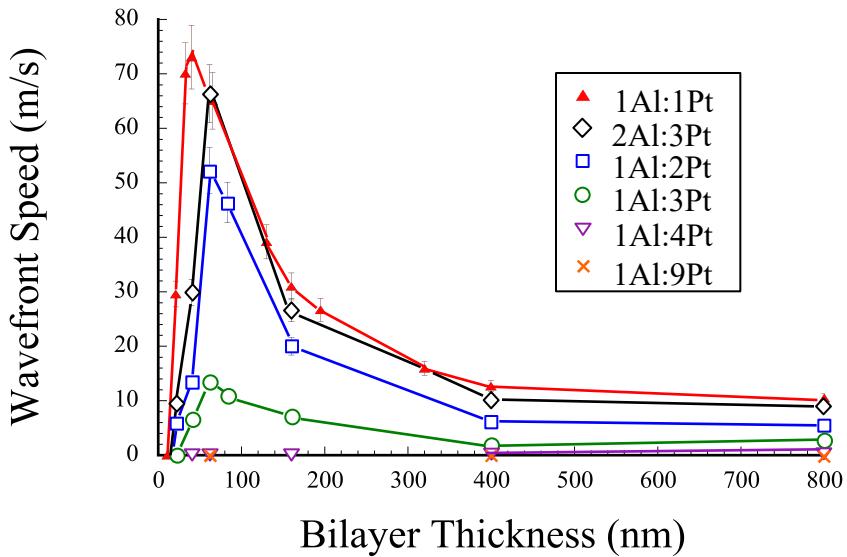
1 Al: 4 Pt  
Bilayer thickness = 800 nm



All other reactive designs,  
(different molar ratios,  
bilayer thicknesses)

Unstable modes predicted near concentration limits: A.S. Rogachev, F. Baras, et al. Doklady Physics 53 (2008).

# Wavefront speed varies with bilayer thickness and stoichiometry.



- Zero speed means multilayer could not be ignited (multiple attempts).
- The range of reactive stoichiometry spans 20 to 80 at.% Pt (including endpoints).

# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

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$$v_{\text{flame}}^2 = \left( \sum_{n=odd} \frac{k_n^2}{\alpha_n^2} \right)^{-1} \frac{4A RT_{\max}^2 \lambda^2}{E(T_a - T_o)} \exp(-E/RT_{\max})$$

A = Arrhenius prefactor

R = gas constant

$\lambda$  = thermal diffusivity (in plane)

E = activation energy

$T_{\max}$  = maximum temperature

$T_o$  = ambient temperature

$k_n$  = Fourier coefficients

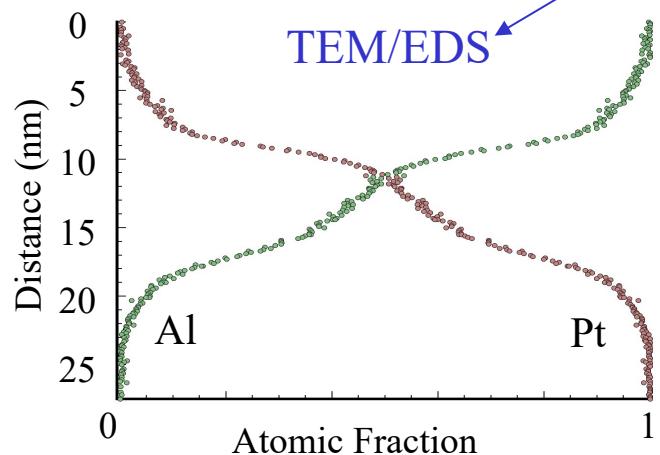
$\alpha_n$  = Fourier eigenvalues

$T_a$  = adiabatic temperature

# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

---

$$v_{\text{flame}}^2 = \left( \sum_{n=\text{odd}} \frac{k_n^2}{\alpha_n^2} \right)^{-1} \frac{4A RT_{\max}^2 \lambda^2}{E(T_a - T_o)} \exp(-E/RT_{\max})$$

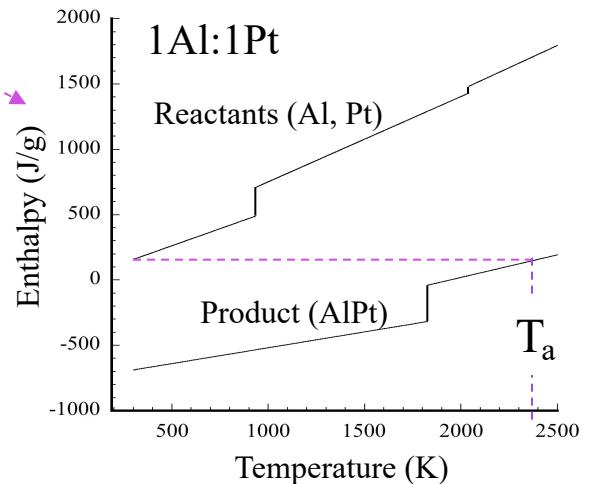


# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

---

$$v_{\text{flame}}^2 = \left( \sum_{n=\text{odd}} \frac{k_n^2}{\alpha_n^2} \right)^{-1} \frac{4A \, RT_{\max}^2 \lambda^2}{E(T_a - T_o)} \exp(-E/RT_{\max})$$

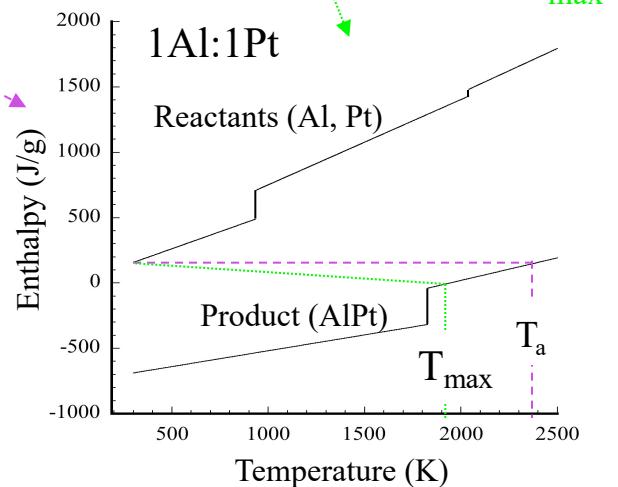
Enthalpy – Temp.  
Diagrams



# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

$$v_{\text{flame}}^2 = \left( \sum_{n=\text{odd}} \frac{k_n^2}{\alpha_n^2} \right)^{-1} \frac{4A \, RT_{\max}^2 \lambda^2}{E(T_a - T_o)} \exp(-E/RT_{\max})$$

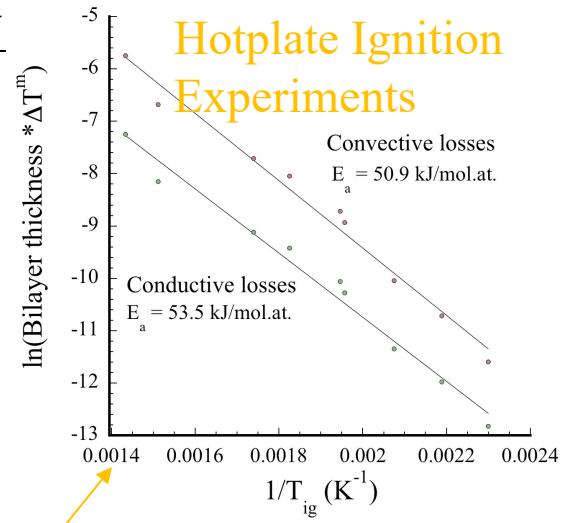
Enthalpy – Temp.  
Diagrams



# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

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# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

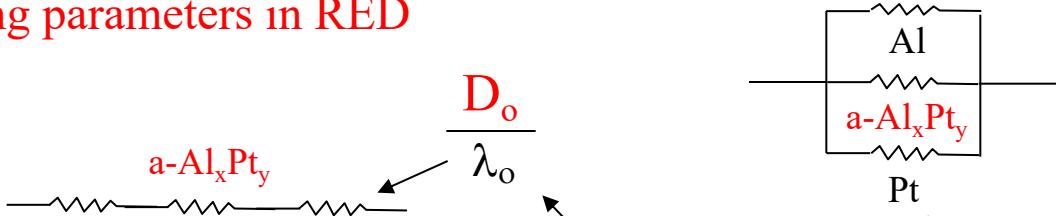
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Resistor Networks

$$v_{\text{flame}}^2 = \left( \sum_{n=\text{odd}} \frac{k_n^2}{\alpha_n^2} \right)^{-1} \frac{4A RT_{\max}^2 \lambda^2}{E(T_a - T_o)} \exp(-E/RT_{\max})$$

# Attempts to utilize the analytical model by Mann et al. to predict wavefront speeds.

Fitting parameters in RED

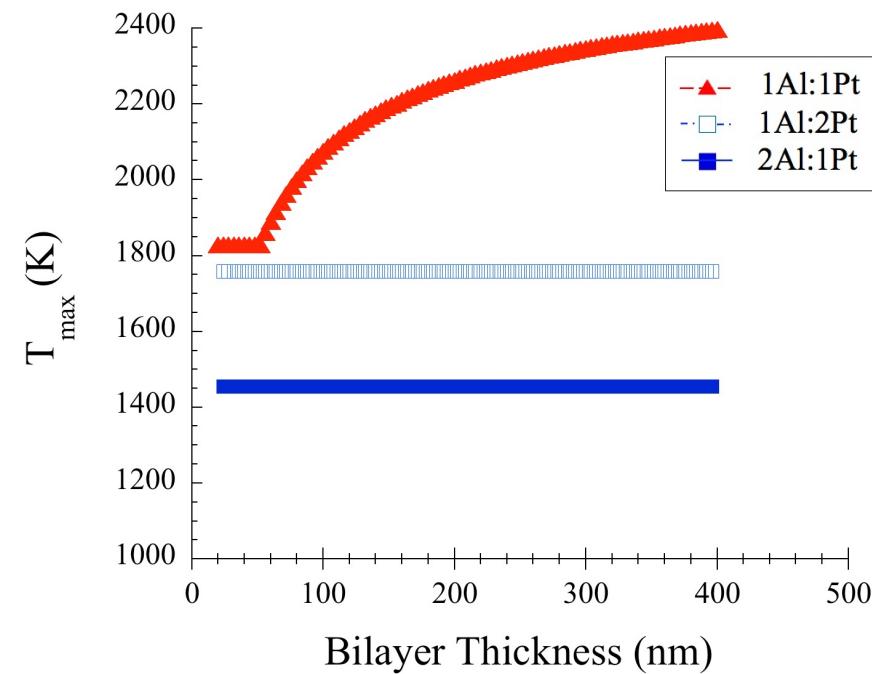
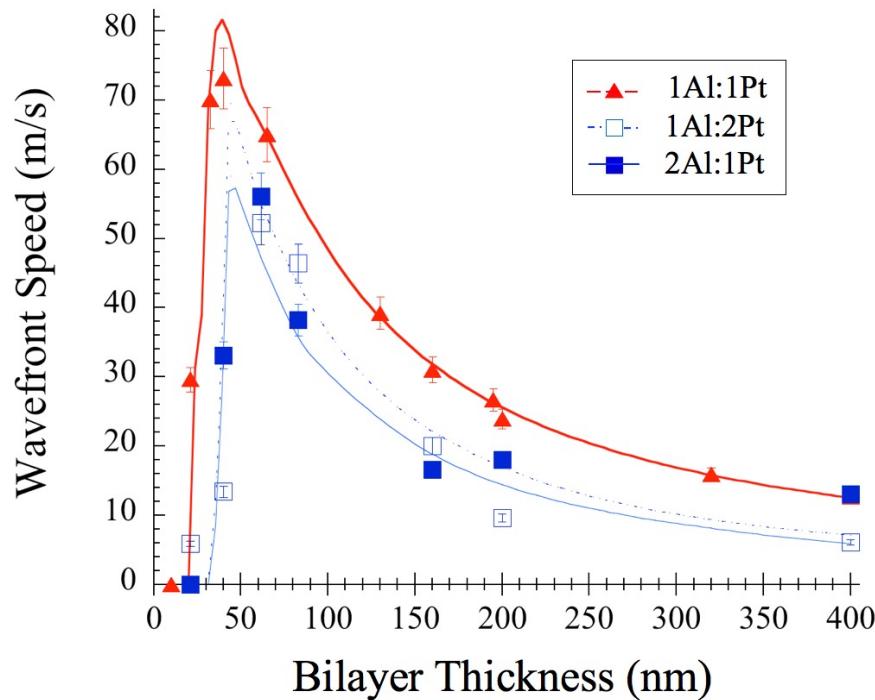


The diagram shows two resistor networks. The left network consists of a horizontal line with a wavy segment labeled 'Al' and a straight segment labeled 'Pt'. A red label 'a-Al<sub>x</sub>Pt<sub>y</sub>' is placed above the wavy segment. Two arrows point from the text 'Resistor Networks' to the segments of the network. The right network is a rectangle with a wavy top edge labeled 'Al', a straight middle section labeled 'a-Al<sub>x</sub>Pt<sub>y</sub>', and a wavy bottom edge labeled 'Pt'.

**Resistor Networks**

$$v_{\text{flame}}^2 = \left( \sum_{n=\text{odd}} \frac{k_n^2}{\alpha_n^2} \right)^{-1} \frac{4A RT_{\max}^2 \lambda^2}{E(T_a - T_o)} \exp(-E/RT_{\max})$$

# Predicted propagation speeds match well to measured values (three stoichiometries).

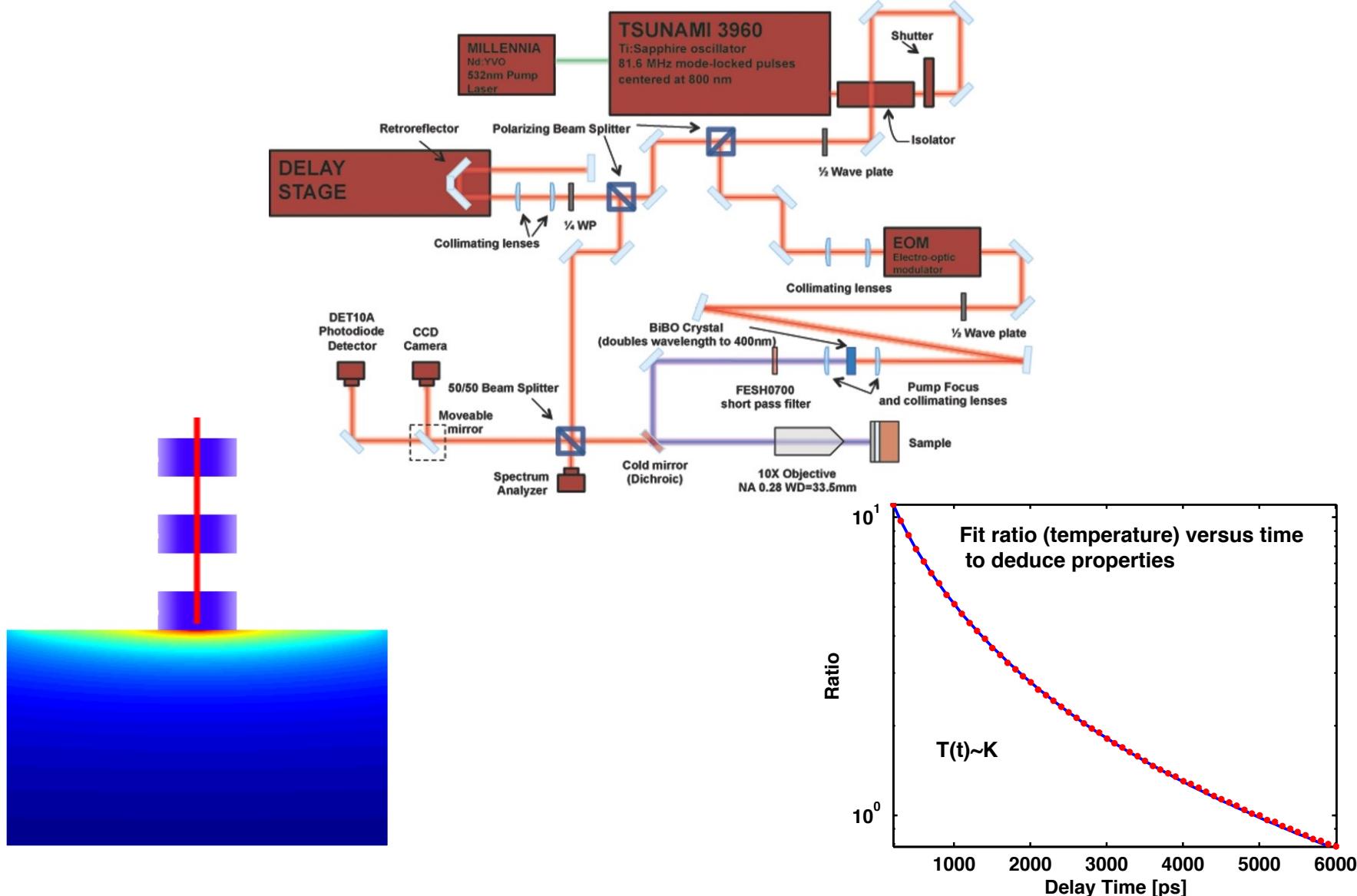


Fit parameters (2):

$$D_o = 1.63 \text{ e}^{-6} \text{ m}^2/\text{s}$$

$$\lambda_{\text{premix}} = 2.8 \text{ e}^{-6} \text{ m}^2/\text{s} \quad (\text{estimate } k = 7 \text{ W/m}\cdot\text{K})$$

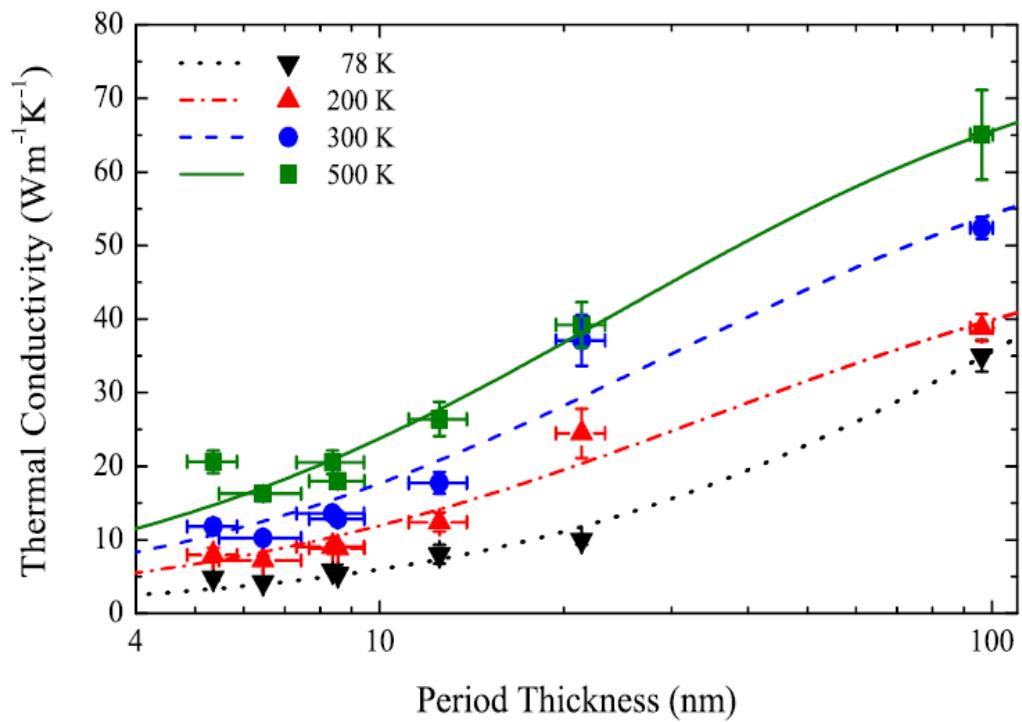
# Time Domain ThermoReflectance (TDTR) for determining cross-plane thermal conductivity



# TDTR has been used previously to determine thermal conductivity of thin film multilayers.

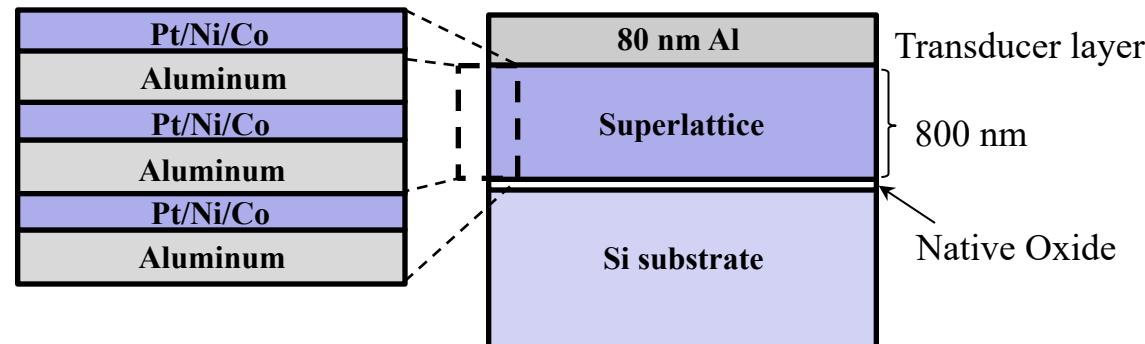
- Cu-Nb does not interdiffuse and so creates “perfect” interfaces.
- Metal multilayers found to obey lumped series resistance model

$$R_{\text{tot}} = \frac{d}{\kappa_{\text{measured}}} = R_0 + \frac{n}{h_{\text{Cu-Nb}}}$$

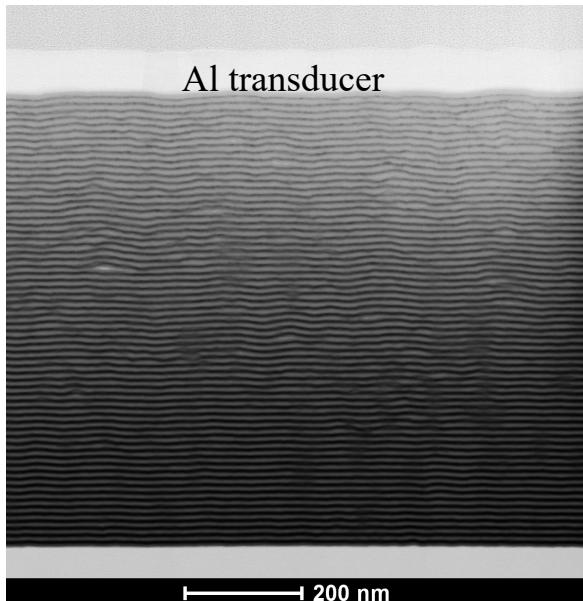


R. Cheaito, K. Hattar, J.T. Gaskins, A.K. Yadav, J.C. Duda, T.E. Beechem, J.F. Ihlefeld, E.S. Piekos, J.K. Baldwin, A. Misra, P.E. Hopkins, *Applied Physics Letters*, 2015, 106, 093114

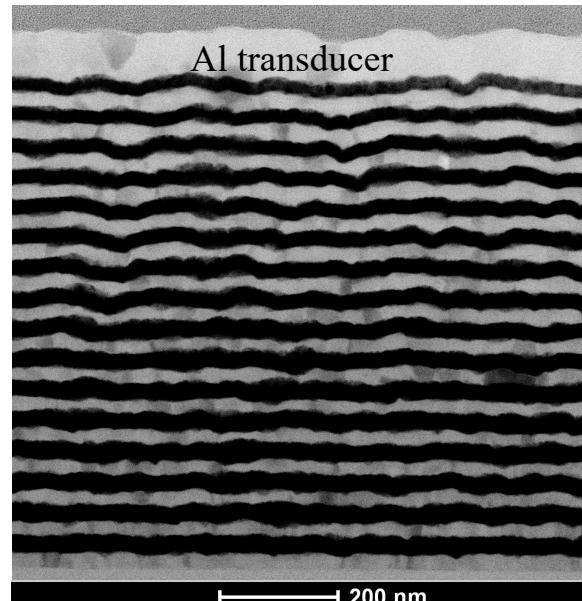
# Thin film test structures for TDTR



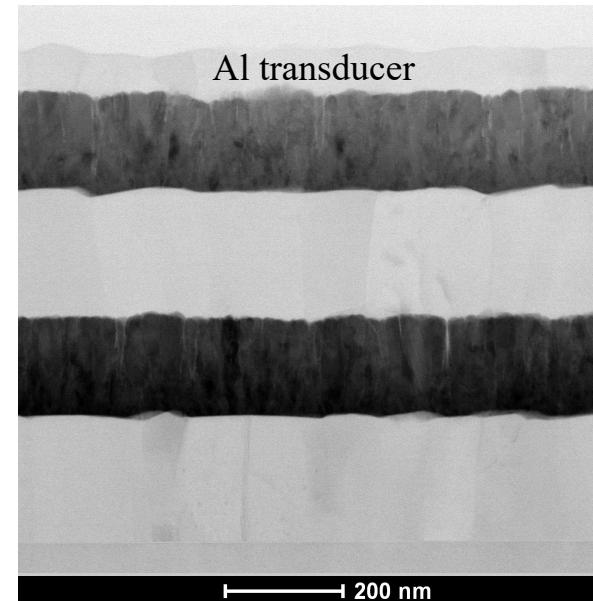
Small  $t_B$



Medium  $t_B$

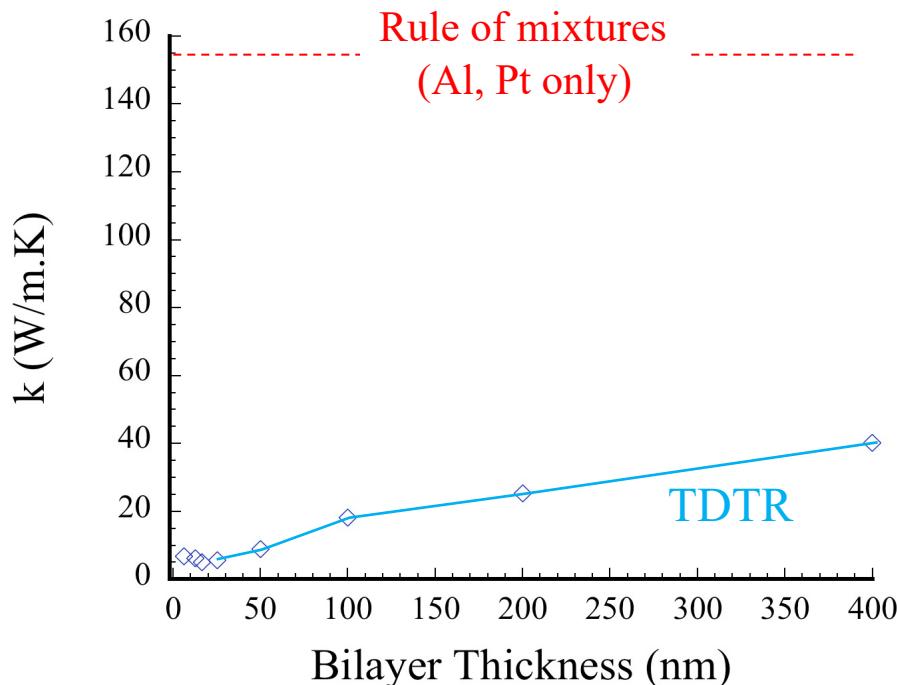


Large  $t_B$



# Measured cross-plane thermal conductivity

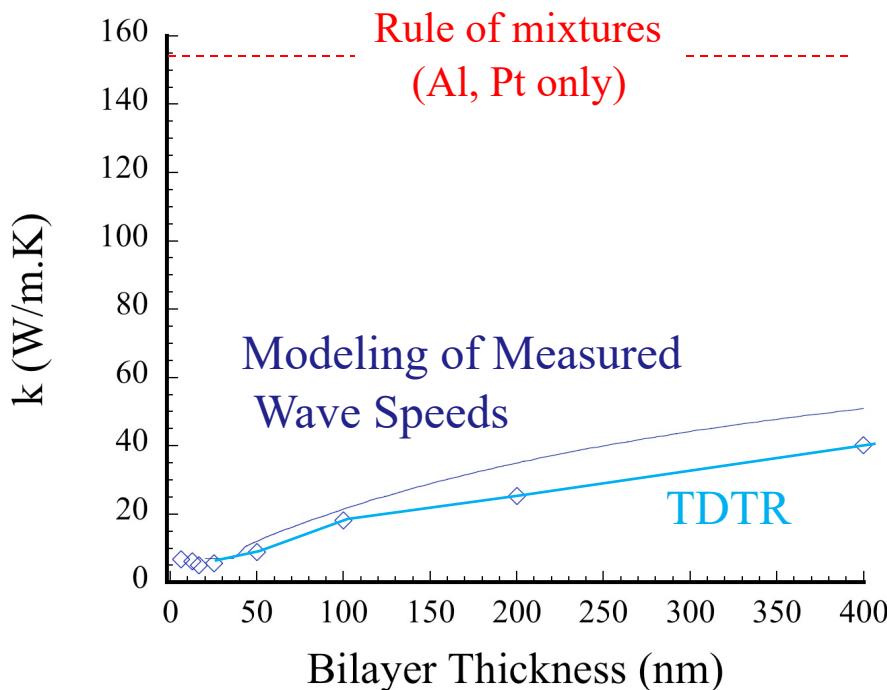
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- Far below the rule – of – mixtures estimate
  - 154 W/m·K
- $k$  varies with bilayer thickness
- Similar trend and values predicted for series resistor network used in velocity modeling.

# Measured cross-plane thermal conductivity

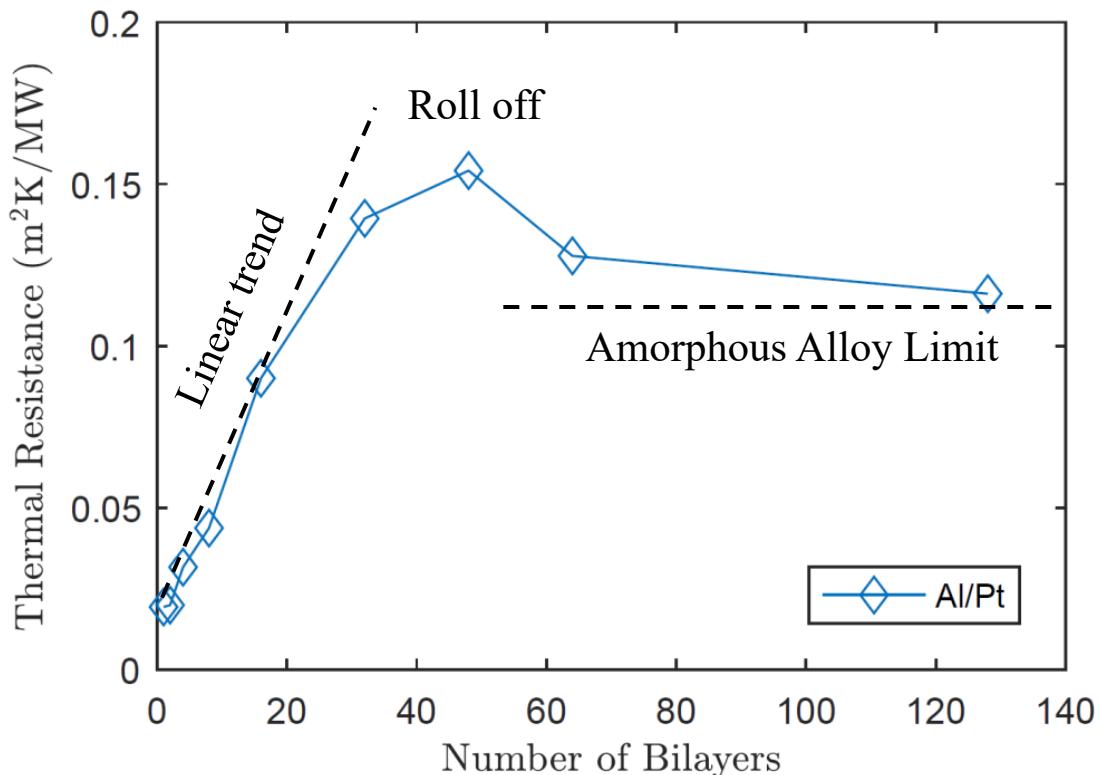
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- Far below the rule – of – mixtures estimate
  - $154 \text{ W/m}\cdot\text{K}$
- $k$  varies with bilayer thickness
- Similar trend and values predicted for series resistor network used in velocity modeling.

# Does the series resistance model work?

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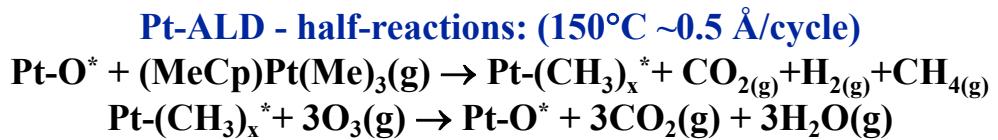
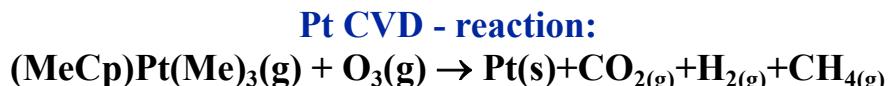
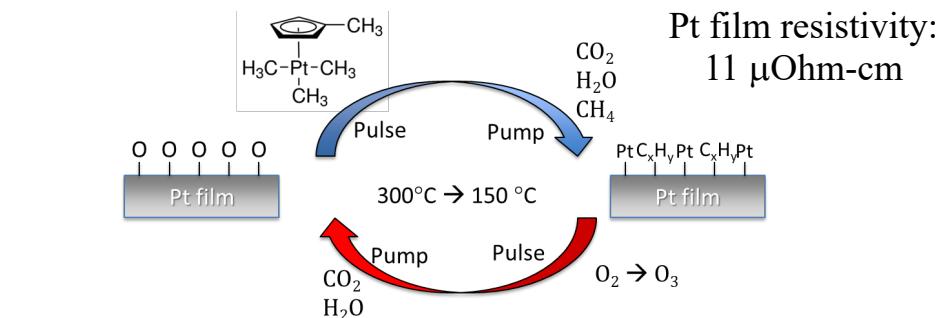
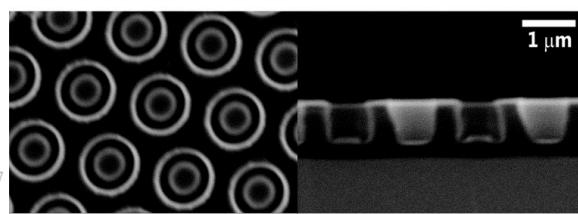
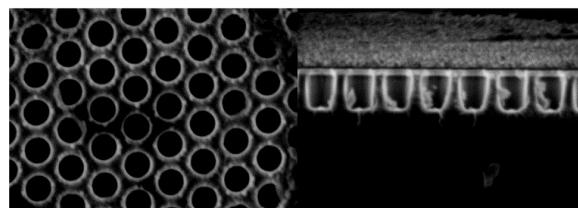
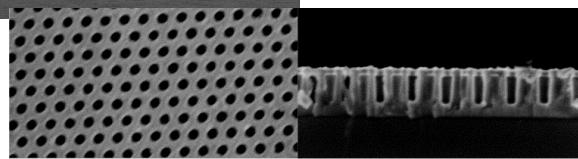
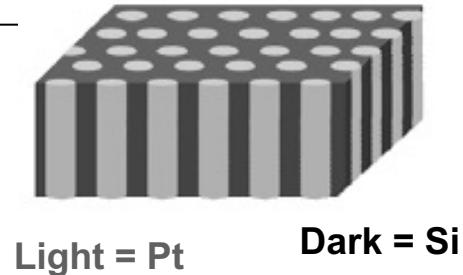
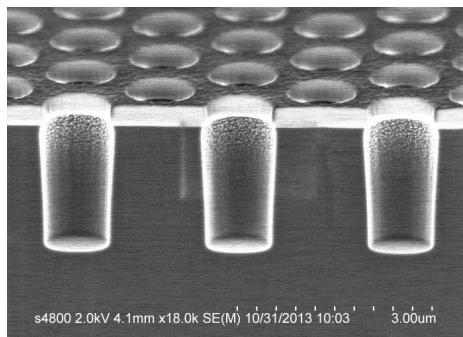


- Strong linear trend indicates model behavior
- Roll off indicates coherent transition
- Maximum resistance of metal multilayer greater than amorphous analogue

Detailed discussion of thermal can continue at a Poster tonight  
(ES09.03.36 Beechem, Saltonstall, Abere, Adams)

# Future direction: 2-D periodic reactive coatings fabricated by Bosch etching and ALD.

Cross Section showing partially etched holes,  $\varnothing = 1 \mu\text{m}$



# Summary

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- Various techniques used for thin film fabrication and surface engineering provide the necessary control of stoichiometry, purity and dimension for detailed studies of structure-composition-property relationships in reactive materials.
- The range of reactive stoichiometry for bimetallic multilayers is large when periodicity is made small (nm scale)
  - Al/Pt: reactive designs span at least 20 to 80 at.% Pt.
  - Attributed to a substantial heat of formation and  $T_a$  across molar range
- Heats, ignition temperatures and wavefront speeds vary with stoichiometry
- Past analytical models have been used to predict wavefront speeds for different stoichiometries that match experimental measurements.
- Thermal conductivity (cross plane) varies with bilayer thickness, overall chemistry and possibly the characteristics of the premixed zone.